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05452 (US). **RANKIN, Jed, H.** [US/US]; 1000 River Street, Essex Junction, VT 05452 (US).

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(74) Agent: **KOTULAK, Richard, M.**; Intellectual Property Law 972E, 1000 River Street, Essex Junction, VT 05452 (US).

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(71) Applicant (*for all designated States except US*): **INTERNATIONAL BUSINESS MACHINES CORPORATION** [US/US]; New Orchard Road, Armonk, NY 10504 (US).

(72) Inventors; and

(75) Inventors/Applicants (*for US only*): **ANDERSON, Brent, A.** [US/US]; 1000 River Street, Essex Junction, VT 05452 (US). **BRYANT, Andres** [US/US]; 1000 River Street, Essex Junction, VT 05452 (US). **NOWAK, Edward, J.** [US/US]; 1000 River Street, Essex Junction, VT

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(54) Title: SPACER FILL STRUCTURE, METHOD AND DESIGN STRUCTURE FOR REDUCING DEVICE VARIATION

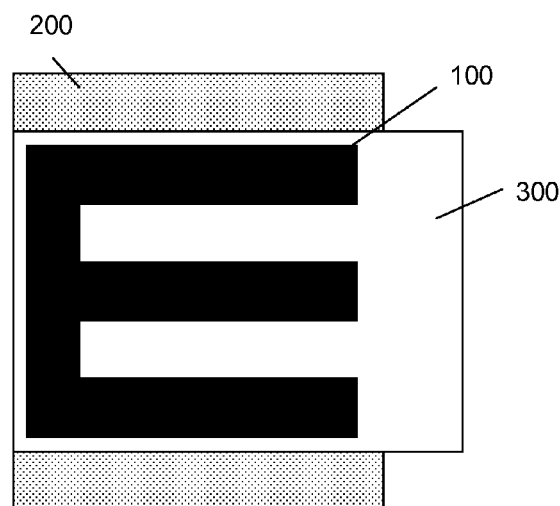


FIG. 1a

(57) Abstract: A design structure (100, FIG. 1a) is provided for spacer fill structures (100 and 300) and, more particularly, spacer fill structures (100 and 300), a method of manufacturing and a design structure for reducing device variation is provided. The structure includes a plurality of dummy fill shapes (100) in different areas of a device which are configured such that gate perimeter to gate area ratio will result in a total perimeter density being uniform across a chip.



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